ABSTRACT

A semiconductor waste gas processing device comprises a flame path through a waste gas combustion chamber, a head section on a top of the waste gas combustion chamber, and a waste gases outlet. The flame path comprises at least one layer of fuel spray ring; each fuel spray ring having a respective fuel room formed in the head section and being connected to a fuel source line for supplying fuel gas; a secondary flame ring of each fuel spray ring having a plurality of secondary flame apertures; a tapered flame jet which is communicable with the waste gas combustion chamber being formed in a lower end of the flame path and an igniter being installed in the flame path.